

COMPONENTS FOR SURFACE ANALYSIS

Ultraviolet Source UVS 300

- Duoplasmatron discharge
- High flux $> 2 \cdot 10^{16}$ Photons / sr · s
- Adjustable He I / He II ratio
- Excellent absolute He II intensity
- Single stage differential pumping
- Special capillary option for
small spot size $< 500\mu\text{m}$ and
high sample current $> 500\text{nA}$



Ultraviolet Source UVS 300

The UVS 300 generates a high density plasma by guiding the electrons extracted from a hot cathode filament along the lines of a strongly inhomogeneous magnetic field towards a small discharge region (duo-plasmatron principle). The strong vacuum ultraviolet radiation is extracted from the cathode side by the combination of a metal and quartz capillary.

Easy use is assured by one stage differential pumping and an integrated microvalve for a filament exchange without affecting the vacuum.

Application:

- Ultraviolet photoelectron spectroscopy (UPS)

Technical Data:

- High intensity photocurrent > 200nA
- Differential pumping
- Water cooling 0.5bar, 1.5l/min
- Mounting flange DN35CF (2.75" OD)
- Insertion depth 166mm
- Bakeable up to 100°C
- High intensity of atomic and ionic lines, e.g. He II
- Other operational gases and capillaries possible
- Weight 12kg

Power Supply

UVS 300-A

- High thermal and electrical stability
- Constant voltage / current mode
- Interlocks: flow sensor, cathode temperature



- 19" (W) x 182mm (H), 8.7kg
- 100/115/200/230V, 600VA, 50-60Hz

Options

Special capillary

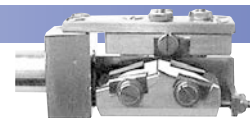
- Small spot size < 500µm
- High sample current > 500nA

Monochromator

Leak valve

Gas inlet

Polarizer



- For measurements with linearly polarized VUV light
- Triple mirror construction
- Polarization degree > 90%
- In situ switchable polarized / nonpolarized

Pumping lines

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